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CCS H 80



**NATIONAL STANDARD OF THE
PEOPLE'S REPUBLIC OF CHINA**

GB/T 24575-2009

**Test method for measuring surface sodium, aluminum,
potassium, and iron on silicon and epi substrates by secondary
ion mass spectrometry**

硅和外延片表面Na、Al、K和Fe的二次离子质谱检测方法
(English Translation)

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What this standard covers

This standard specifies the silicon and epitaxial wafer surface Na, K and secondary ion mass spectrometry method of Fe, Al. This standard applies to detect Na mirror polished monocrystalline silicon and epitaxial wafer surface by secondary ion mass spectrometry (SIMS), Al, K and Fe total of each metal. This standard test is the total amount of each metal, so the method has nothing to do with the chemical and electrical properties of each metal. This standard applies to all types of doped silicon and dopant concentration. This standard is particularly applicable to the surface of the test piece located on the surface of metal products tainted depth of about 5nm. This standard applies to the surface density range ($10^9 \sim 10^{14}$) atoms/cm² Na, Al, tested K and Fe. The detection limit of the method depends on the count rate limit value or a blank, because of different instruments and different.

Document data

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Standards quoted by this document

ASTM E673; ASTM E122